



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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TC 1700

In re Application of :  
Rajinder DHINDSA et al :  
Serial No. 10/032,279 : Group Art Unit: 1725  
Filed: December 31, 2001 : Examiner: N/A  
For: DUAL FREQUENCY PLASMA PROCESSOR

PRELIMINARY AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS  
Washington, D.C. 20231

Dear Sir:

Preliminary to examination of the above-referenced application, please amend the application:

IN THE SPECIFICATION:

Change the title to --Plasma Processor in Plasma Confinement Region Within a Vacuum Chamber.--

IN THE CLAIMS:

Cancel claims 1-20.

Add the following claims:

52. (NEWLY ADDED) Apparatus for processing a workpiece with a plasma comprising a vacuum chamber having a wall arrangement with a plasma confinement region located in the chamber so it is spaced from the wall arrangement; a gas confinement region having a gas inlet and gas outlet; and a plasma excitation arrangement for coupling a plasma exciting field to gas in the plasma confinement region; the plasma